

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: HASHIMOTO, Hiroshi et al.

Group Art Unit: 2814

Serial No.: 09/960,399

Examiner: Howard Weiss

Filed: September 24, 2001

P.T.O. Confirmation No.: 5652

For: A SEMICONDUCTOR INTEGRATED CIRCUIT AND FABRICATION PROCESS HAVING COMPENSATED STRUCTURES TO REDUCE MANUFACTURING DEFECTS (as amended)

AMENDMENT UNDER 37 CFR §1.111

Commissioner for Patents Washington, D.C. 20231

Sir:

In response to the Office Action dated July 2, 2002, please amend the above-identified application as follows:

IN THE DRAWINGS:

Submitted herewith is a Request for Approval of Drawing Corrections, along with proposed drawing corrections to Figures 1A-30B, as marked in red ink.

The applicants respectfully request that the proposed drawing corrections submitted herewith be approved by the Examiner, and that the outstanding objection to the drawings be withdrawn.